

IN THE SPECIFICATION

Please substitute the following paragraph for the one on page 8, lines 7-20.

Aside from forming the lower extremity of the enclosure 114, the dome 106 also defines a surface 212 that is external to the chamber processing environment that supports an RF antenna 210. Specifically, a single length of a conductor (i.e., a copper coil) is positioned at the circumference of the dome 106 and coiled radially inward forming multiple turns. The coil can have separate turns with each turn having a different radius or can spiral radially inward with a continuously changing radius for its different turns. The antenna coil covers approximately 2/3 of the support surface 212. As can be seen in Figures 1-4, the antenna 210 covers at least a portion of the external surface 212 of the dome or ceiling 106 that substantially faces the substrate 110. The antenna 210 is coupled to a high power RF power source (not shown) for the purpose of ionizing a process gas into a plasma in the process chamber 100. The antenna 210 and the RF source form a decoupled plasma source. Preferably, the dome 106 is opaque quartz or a ceramic such as alumina. Such materials are substantially transparent to infrared wavelengths that are produced by lamps within the temperature control unit. The heat produced by these emissions are used to heat the chamber environment. As such, the dome 106 is permeable to the magnetic fields from the antenna 210 which control and enhance plasma characteristics. Proximate the apex 123 of the dome 104, the opening 122 is formed. As such, the beams from and to the collimating assembly 126 pass through the opening 122 and into and out of the process chamber 100.